CHEMICAL CLEAN/ETCH

MODEL CESx133AR

DESCRIPTION: MODEL CESx133AR
The **highly efficient** Model CESx133AR is the ideal for Cleaning and Etching Wafers, Photomask, and Substrates. The **very reliable** and **cost effective** system utilizes proven assortment of technologies on individual or multiple media. The CESx133AR can be configured with several process dispense options from Brush for Sulfuric Peroxide, Surfactant, and/or DI-H₂O as well as for Surface Agitation to Expedite Reactions; Megasonic Nozzles for DI-H₂O or Chemistries; Low pressure nozzles for chemistry dispenses; Heaters for chemistries and DI-H₂O; Nitrogen Assist and much more. The Rapid and Effective Drying technique combines Variable Spin Speeds; optional Heated DI-H₂O; and Nitrogen Assist. The System is very safe, having “Rinse to pH” before access to the substrate to minimize exposure to chemistries. The System is designed to be Automation Ready (AR)

FEATURES: CONTROL & SAFETY
- System Designed for Significant Control & Safety
- Up to Twenty One (21) Inches on Diagonal/Diameter or Multiples of Smaller Size Substrates.
- Main Spindle Assembly having DC Brushless Servo Motor for precise speed control & indexing.
- Adjustable Arm Speed and Travel Positions with Arms of Teflon Coated Stainless Steel.
- Radially Exhausted Chamber for Maximum Laminar Flow with N₂ feed at Top of the lid.
- DI-H₂O Heater for Clean & Dry Assist.
- Process containment wetted surfaces of chemically compatible material either PVDF or optional PTFE.
- Stand-alone Polypropylene Cabinet or optional (shown) Stainless Steel Frame & Skins.
- Microprocessor Control Capable of Retaining Thirty (30) Recipes having thirty (30) Steps each in Memory. Both number of Recipes & Steps are expandable upon request.
- Built in Safety Interlocks & Double Containment.
- Rinse to pH of entire process area & substrate with interlocks to prohibit access to process area & control Drain and Spindle Speed till safe.
- Push Button Lid Open/Close.
- Touch Screen Graphic User Interface (GUI) with Ease of Programming & Security Lockouts with On-Screen Error Reporting.
- Drain Diverter Valves for Chemical & House Drains

OPTIONS: UP TO FOUR OSCILLATING DISPENSE ARMS
- Various sizes & types of chucks for Wafers, Photomask, and other Substrates.
- Auto Up/Down Oscillating Adjustable Self Cleaning Brush Assembly for chemical, Surfactant, & DI-H₂O Dispenses.
- Oscillating Megasonic Nozzles & Megpies for DI-H₂O or Chemical Dispense Arm.
- Fixed or Oscillating Low Pressure Dispense with various Nozzles for DI-H₂O &/or Chemistries.
- Chemical Cabinet with weight Scale Dispense Canisters, Digital Flow Meter & Pump.
- Heater for Chemical & DI-H₂O Dispenses.
- Secondary Containment With Leak Detection
- Point of Use Mixing Systems.
- FM4910 Fire Retardant Cabinet & Process Area Materials
- Designed to SEMI S2/S8 guidelines.

ULTRA Equipment Company, Inc.
41980 Christy Street, Fremont, CA 94538
TEL: (510) 440-3900  FAX: (510) 440-3920
URL: www.ultrat.com